



Silicon Nanophotonics

- 现代工程与应用科学学院
 - 2020-4-22



主要内容



- ●简介
- ●器件及应用
- ●小结



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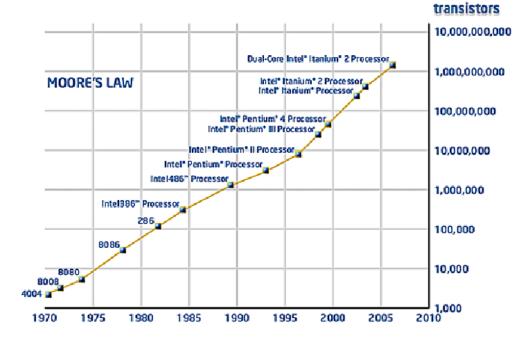


背景介绍

摩尔定律



1984 J.P. Goodman提出光互 联(Ge, InP, GaAs, Si...)



Si光互联可能是最有 前景的方法

制备工艺与微电子工艺兼容

成本低

在通信波段损耗低

折射率高(3.4) →



小尺寸





早期工作

IEEE JOURNAL OF QUANTUM ELECTRONICS, VOL. QE-22, NO. 6, JUNE 1986

All-Silicon Active and Passive Guided-Wave Components for $\lambda = 1.3$ and $1.6 \mu m$

Loss: 5-20 dB/cm

RICHARD A. SOREF, SENIOR MEMBER, IEEE, AND JOSEPH P. LORENZO

OPTICAL CHANNEL WAVEGUIDES IN SILICON DIFFUSED FROM GeSi ALLOY

Indexing terms: Optoelectronics, Optical waveguides, Silicon

A technique for fabricating low-loss and polarisationindependent channel waveguides in silicon is reported. The waveguides are obtained by Ge-indiffusion using either a GeSi alloy or a system of alternating Ge and Si layers. Typical fabrication parameters for single-mode waveguides are given.

Loss: 4 dB/cm

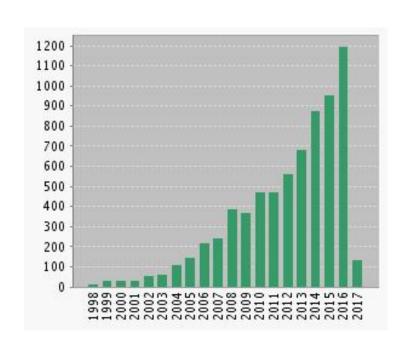
ELECTRONICS LETTERS 26th October 1989 Vol. 25 No. 22



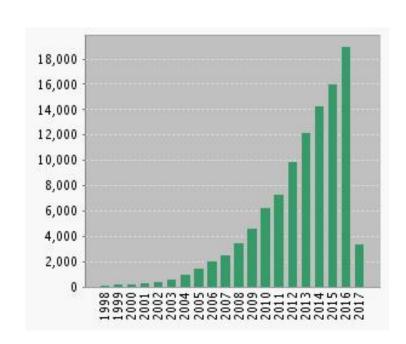


研究现状

每年出版的文献数



每年的引文数

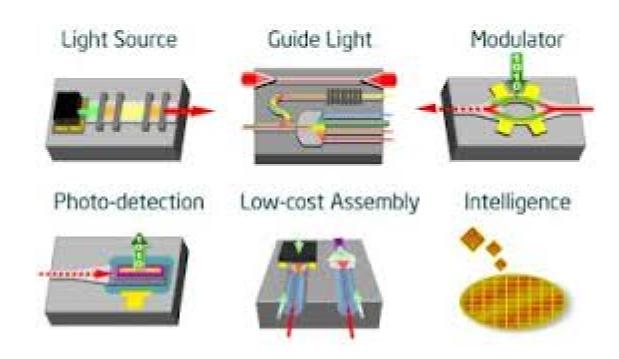


关键词: Silicon Photonics (ISI Web of Knowledge)





Building blocks



Intel



主要内容



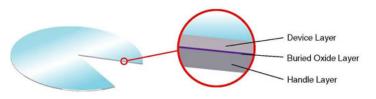
- ●简介
- ●器件及应用
- ●小结

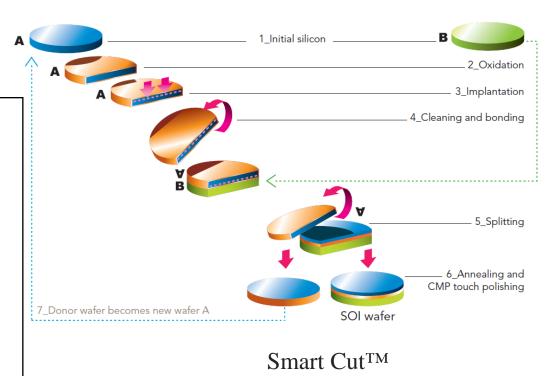




SOI wafer

Silicon On Insulator Wafers (SOI)





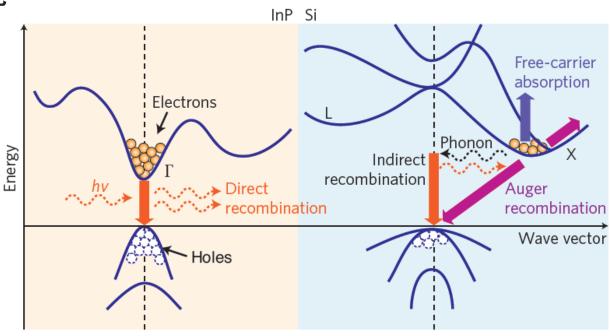






光源-硅基激光

硅的局限 (最大问题)



Energy band diagrams in InP and silicon crystals

解决方法

拉曼激光,外延生产、复合结构





光源-硅基激光 拉曼激光

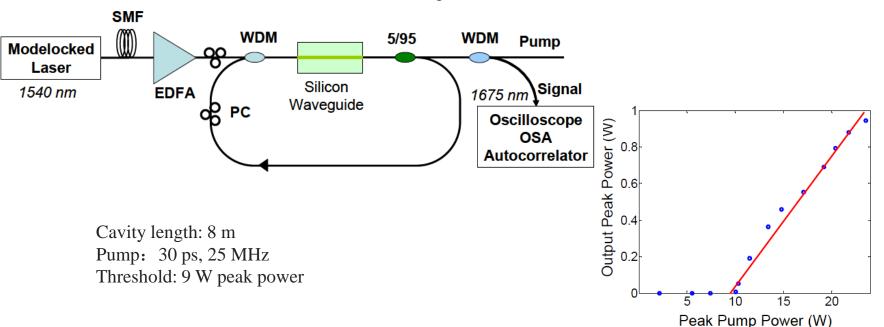
Demonstration of a silicon Raman laser

2004.10

Ozdal Boyraz and Bahram Jalali

第一个硅拉曼激光

Optoelectronic Circuits and Systems Laboratory
University of California, Los Angeles
Los Angeles, CA 90095-1594







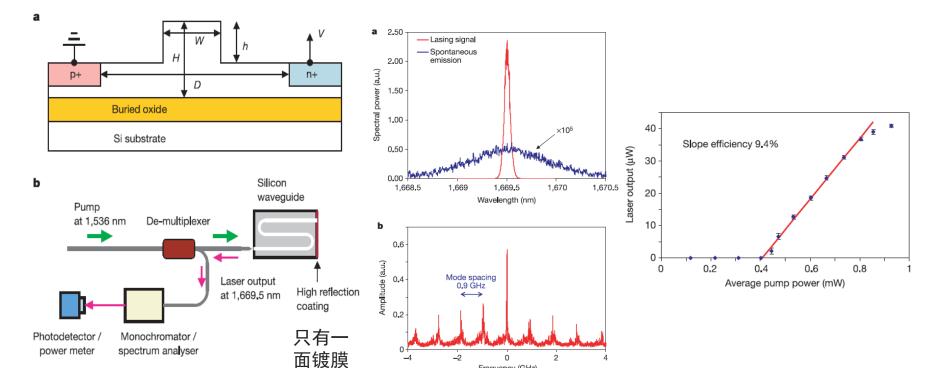
光源-硅基激光

拉曼激光

An all-silicon Raman laser

Haisheng Rong¹, Ansheng Liu¹, Richard Jones¹, Oded Cohen², Dani Hak², Remus Nicolaescu¹, Alexander Fanq¹ & Mario Paniccia¹

2005.1



Frequency (GHz)

Pulse pump: 130 ns, 10 KHz

Cavity length: 4.8 cm



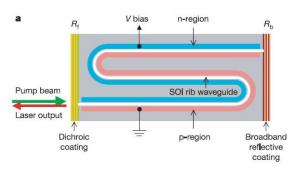


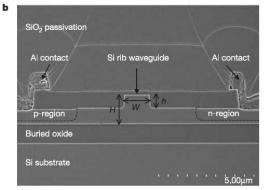
光源-硅基激光 拉曼激光

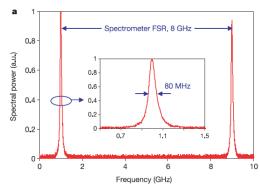
A continuous-wave Raman silicon laser

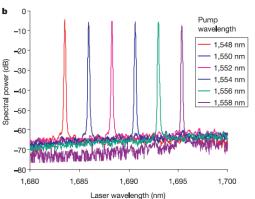
2005.2

Haisheng Rong¹, Richard Jones¹, Ansheng Liu¹, Oded Cohen², Dani Hak², Alexander Fang¹ & Mario Paniccia¹









Threshold: 180 mW

Cavity length: 4.8 cm

H. Rong et. al., Natute 433, 725 (2005).



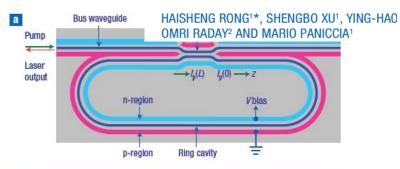


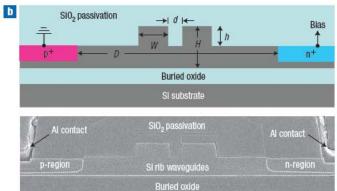
光源-硅基激光 拉曼激光

Low-threshold continuous-wave

Raman silicon laser

2007.4





Cavity length: 3.0, 1.5 cm

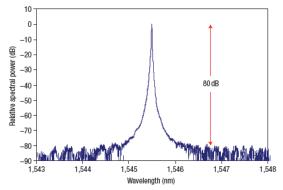
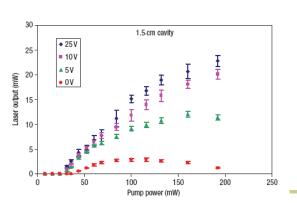


Figure 5 Raman silicon laser spectrum. The laser spectrum was measured with a grating-based optical spectrum analyser with a resolution of 0.01 nm, showing single-mode lasing with side-mode suppression of >80 dB.



Threshold: \sim 20 mW

Pump light: On resonance

H. Rong et. al., Nat. Photon. 1, 232 (2007).



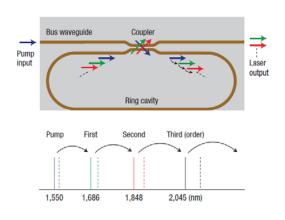


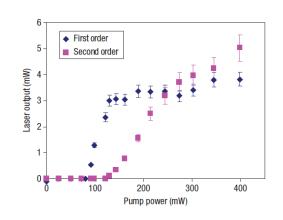
光源-硅基激光 拉曼激光

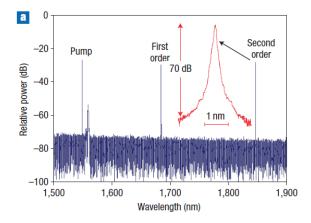
A cascaded silicon Raman laser

2008.3

HAISHENG RONG^{1*}, SHENGBO XU¹, ODED COHEN², OMRI RADAY², MINDY LEE¹, VANESSA SIH¹ AND MARIO PANICCIA¹







Cavity length: 3.0 cm

 $Q: 3.4*10^6$

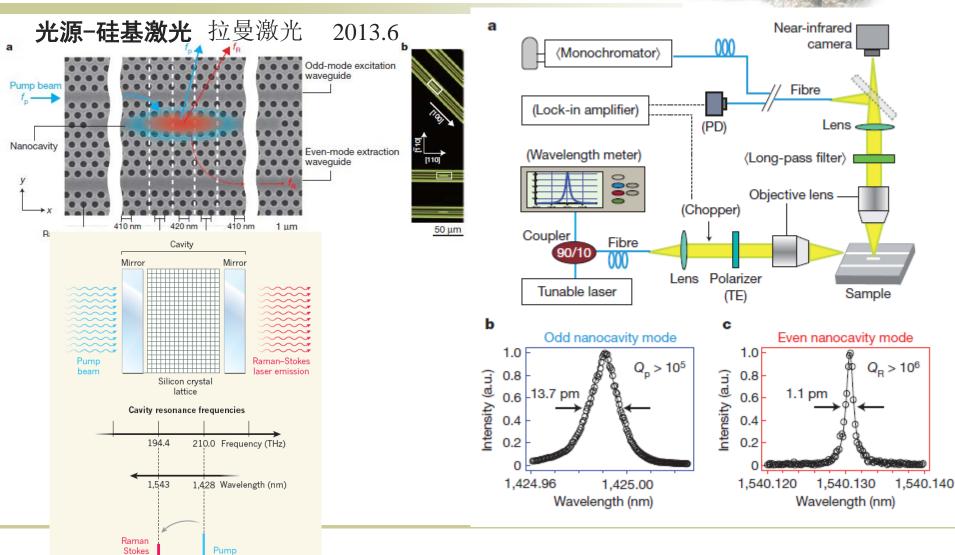
Threshold: 80 mW, first order raman 120 mW, second order raman

Near to mid-IR

Pump light: On resonance







Frequency (THz)

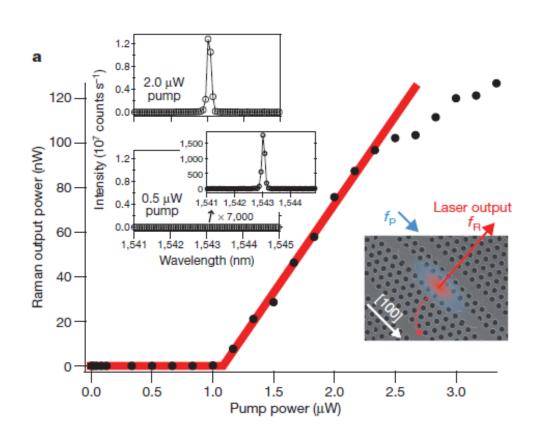
15.6 THz

Y. Takahashi et. al., Nature. 498, 470 (2013).





光源-硅基激光 拉曼激光



Threshold: ${\sim}1\,\mu\text{W}$





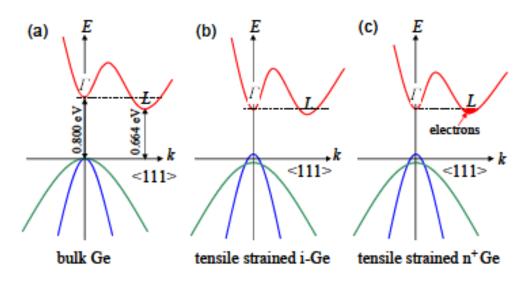
光源-硅基激光

Ge-on-Si laser

Energy band engineering of Ge

Direct- and Indirect-Bandgap Semiconductors

Semiconductors for which the conduction-band minimum energy and the valence-band maximum energy correspond to the same value of the wavenumber k (same momentum) are called **direct-bandgap** materials. Semiconductors for which this is not the case are known as **indirect-bandgap** materials.



Difference: 136 meV

Reduce: 115 meV

Heavy n-doping

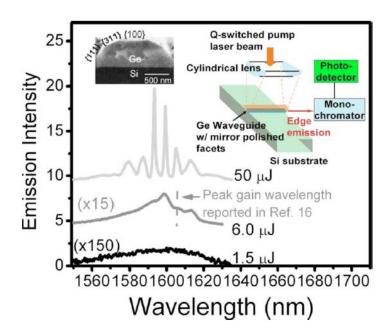




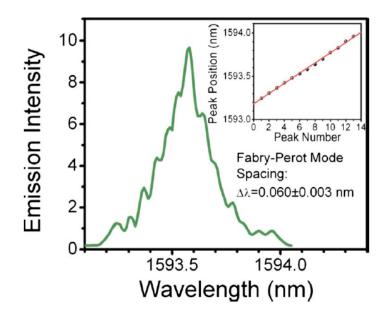
光源-硅基激光

Ge-on-Si laser

Ge-on-Si laser operating at room temperature



Pump: 1064 nm, 1.5 ns, 1 kHz



Threshold: 30 kW/cm²

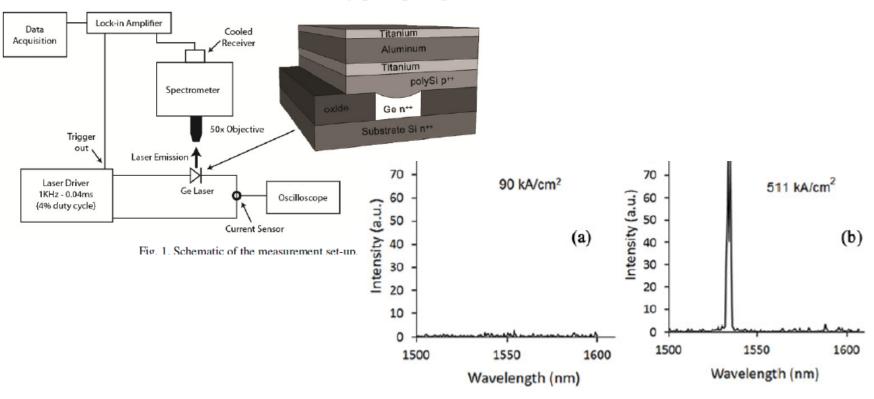




光源-硅基激光

Ge-on-Si laser

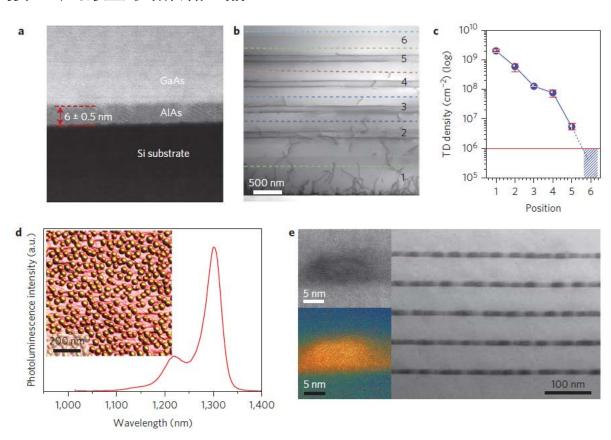
An electrically pumped germanium laser







光源-直接生长的量子点激光器

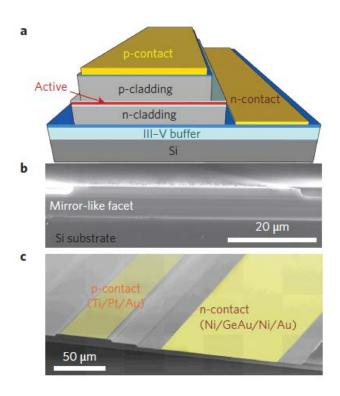


Epitaxial growth and structural characterization of QD lasers.

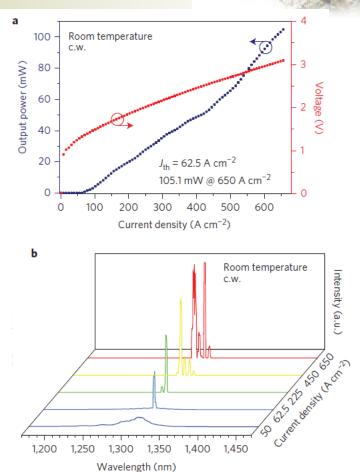




光源-直接生长的量子点激光器



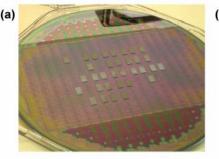
Fabricated III-V laser directly grown on a silicon substrate

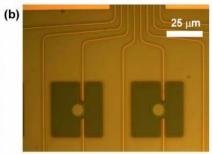


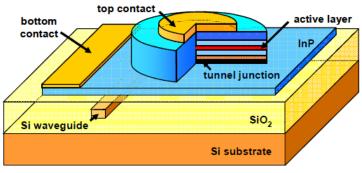
Silicon laser performance characterization





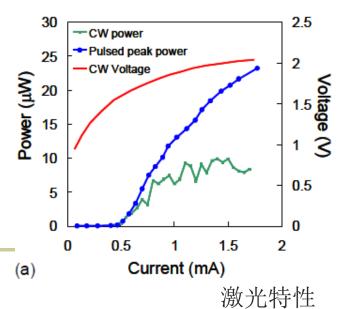






示意图

光源-复合激光器

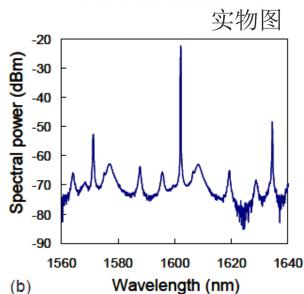


(c) 3 µm

BCB InP-InGaAsP

Si
SiO₂

500 nm



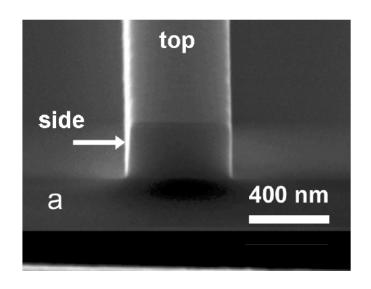
J. V. Campenhout et. al., Opt. Express. 15, 6744 (2007).



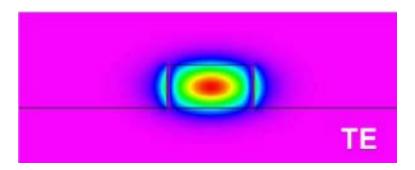


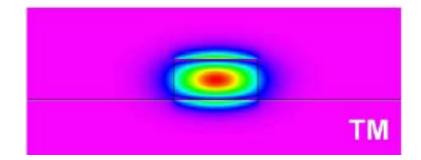
硅基光波导

Silicon waveguide or SOI waveguide



SEM照片





电场分布

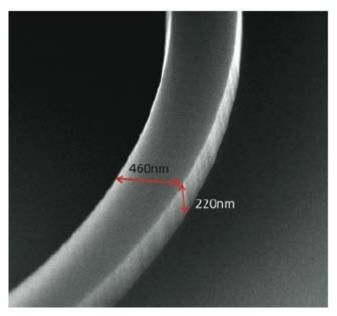
Fabrication: e-beam or optical lighography + reactive ion etching





硅基光波导

损耗



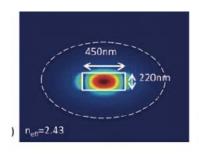
SEM照片

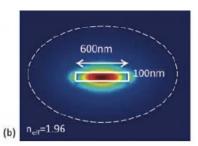
损耗主要来自侧壁粗糙度

减低损耗的办法:



- 1. 减小侧壁的粗糙度;
- 2. 优化波导结构,波导模场与侧壁的相互作用



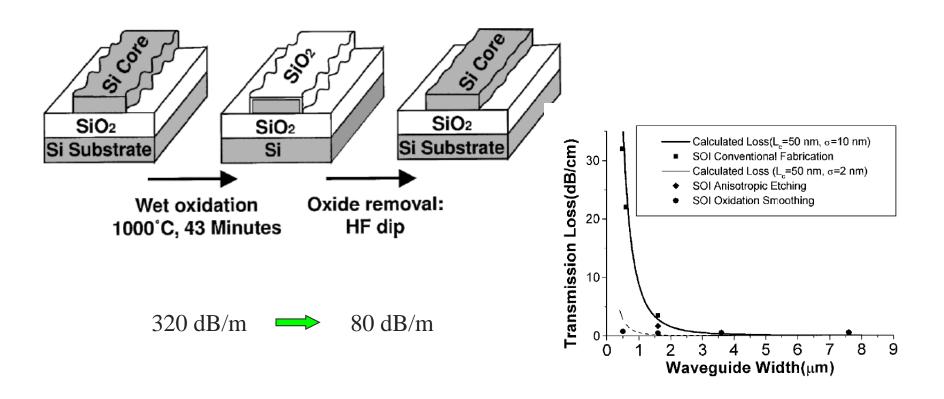






硅基光波导

Fabrication of ultralow-loss Si/SiO₂ waveguides by roughness reduction

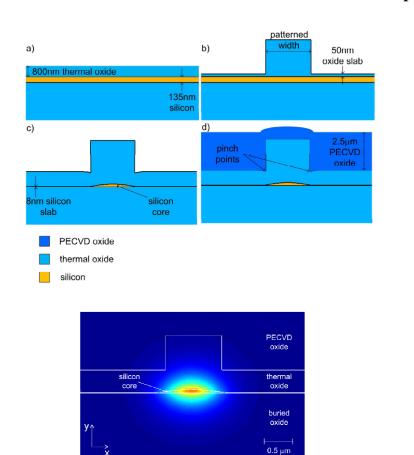


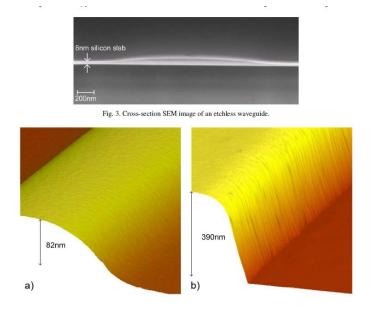




硅基光波导

Low loss etchless silicon photonic waveguides





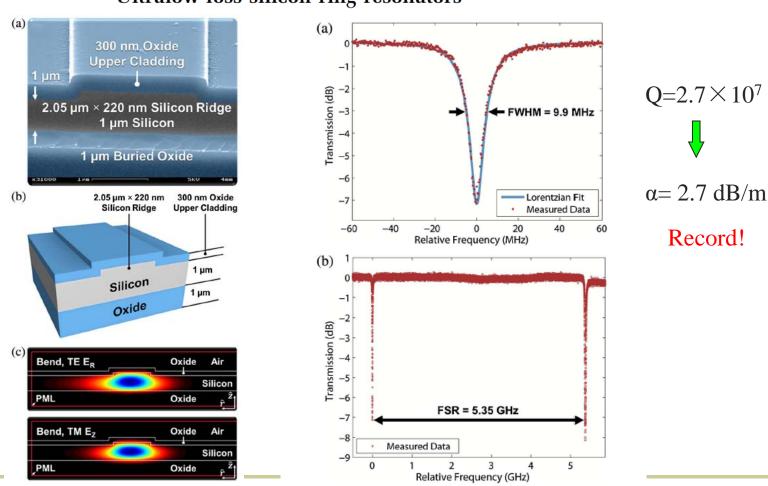
 $\alpha = 30 \text{ dB/m}$





硅基光波导

Ultralow-loss silicon ring resonators

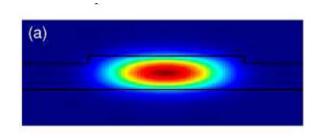


A. Biberman et. al., Opt. Lett. 26, 4236 (2012).





硅基光波导





7mm



 α = 27.4 dB/m

P. Dong et. al., Opt. Express. **18**, 14474 (2010).

Record!

 α = 2.6 dB/m

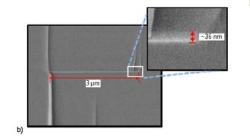
G. Li et. al., Opt. Express. **20**, 12035 (2012).



硅基光波导

氮化硅光波导-1

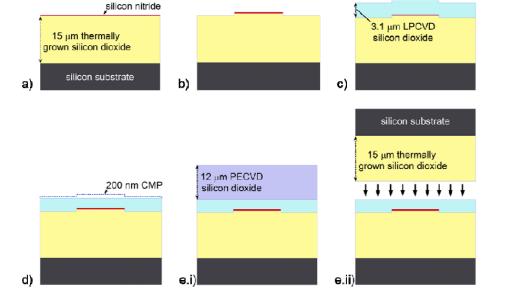
LPCVD

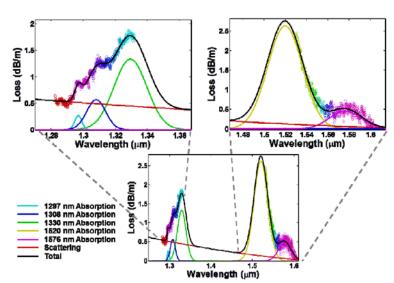


Si₃N₄ thickness:35 nm



Length: 1m





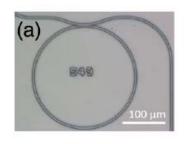
 $\alpha = 0.045 \text{ dB/m} @ 1580 \text{ nm}$

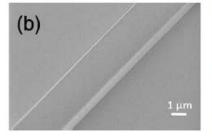


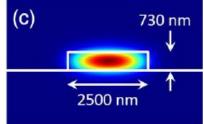


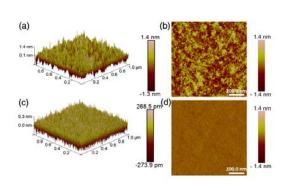
硅基光波导

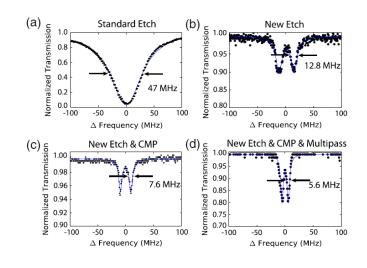
氮化硅光波导-1











 $Q=3.7 \times 10^7$ $\alpha = 0.8 \text{ dB/m}$





硅基光波导

氧化硅回音 壁模光波导

